

In re: Dai et al.  
Group Art Unit No.: 1752  
Filed: March 12, 2004  
Page 2 of 17

**Amendments to the Specification**

Please amend the specification at paragraph [0004] as follows.

**[0004]** To date, extreme ultra-violet (EUV) lithography is one of the most promising next generation lithography technologies that may be used with devices having nanoscale or ~~sub-250~~ sub-250 nm features. SUV lithography may also be used to further push the limits of miniaturization. The goal of EUV lithography has been to create lithography capable of handling a sub-50 nm node. However, the use of EUV lithography has been limited by the absence or lack of materials that can be used in the EUV lithography processes. For instance, a lack of resist materials capable of withstanding currently used etching techniques is problematic.